

1c978 U.S. PTO
09/887035
06/25/01

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Ramkumar SUBRAMANIAN, et al.
Title: TWO MASK PHOTORESIST EXPOSURE PATTERN
FOR DENSE AND ISOLATED REGIONS
Appl. No.: Unassigned
Filing Date: June 25, 2001
Examiner: Unassigned
Art Unit: Unassigned

UTILITY PATENT APPLICATION
TRANSMITTAL

Commissioner for Patents
Box PATENT APPLICATION
Washington, D.C. 20231

Sir:

Transmitted herewith for filing under 37 C.F.R. § 1.53(b) is the nonprovisional utility patent application of:

Ramkumar SUBRAMANIAN
Scott A. BELL
Todd P. LUKANC
Marina V. PLAT
Uzodinma OKOROANYANWU
Hung-Eil KIM

Enclosed are:

- [X] Specification, Claims, and Abstract (18 pages).
- [X] Formal drawings (5 sheets, Figures 1-7).
- [X] Declaration and Power of Attorney (4 pages).
- [X] ✓ Assignment of the invention to ADVANCED MICRO DEVICES, INC.
- [X] Assignment Recordation Cover Sheet.
- [X] Proprietary Information Disclosure Statement with a copy of (2) U.S. Patent Applications.

☒ Request for application not to be published with certification under 35 USC 122(b)(2)(B)(i).

The filing fee is calculated below:

	Claims as Filed	Included in Basic Fee	Extra Claims	Rate	Fee Totals
Basic Fee				\$710.00	\$710.00
Total Claims:	32	- 20	= 12	x \$18.00	= \$216.00
Independents:	3	- 3	= 0	x \$80.00	= \$0.00
If any Multiple Dependent Claim(s) present:				+ \$270.00	= \$0.00
				SUBTOTAL:	= \$926.00
<input type="checkbox"/> Small Entity Fees Apply (subtract ½ of above):					= \$0.00
				TOTAL FILING FEE:	= \$926.00
Assignment Recordation Fee:				+ \$40.00	= \$40.00
				TOTAL FEE	= \$966.00

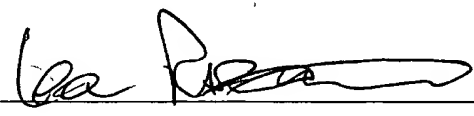
- ☒ A check in the amount of \$966.00 to cover the filing fee and fee for recordation of Assignment is enclosed.
- ☒ The Commissioner is hereby authorized to charge any additional fees which may be required regarding this application under 37 C.F.R. §§ 1.16-1.17, or credit any overpayment, to Deposit Account No. 19-0741. Should no proper payment be enclosed herewith, as by a check being in the wrong amount, unsigned, post-dated, otherwise improper or informal or even entirely missing, the Commissioner is authorized to charge the unpaid amount to Deposit Account No. 19-0741.

Please direct all correspondence to the undersigned attorney or agent at the address indicated below.

Respectfully submitted,

Date June 25, 2001

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REQUEST AND CERTIFICATION UNDER 35 U.S.C. 122(b)(2)(B)(i)

Commissioner for Patents
Washington, D.C. 20231

Sir:


Applicants hereby certify that the invention disclosed in the attached application has not and will not be the subject of an application filed in another country, or under a multilateral agreement, that requires publication at eighteen months after filing.

Applicants hereby request that the attached application not be published under 35 U.S.C. 122(b).

Respectfully submitted,

Date June 25, 2001

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